



Wet Processes Conference

February 12-14, 2007
Santa Clara Convention Center

See Schedule for Revised Presentation Times

NEW TUTORIAL SESSION ON MONDAY 9:00am – 11:00am

*“Useful Measurements For Detecting Trace Metal Contaminants
In Semiconductor Processing”*

REGISTER TODAY @ <http://www.spwcc.com>!!!

SPECIAL: Mark your Registration Form MKB and Use Early Reg Prices Thru Feb 2nd!!!

SPWCC will again bring together international industry professionals sharing **NEW** information and the methods you need to achieve the **excellence in results** your company demands!

Hear the experts address issues affecting wet processes using ultrapure water, chemicals and chemical mixes for the semiconductor industry!

UPDATED TECHNICAL CONFERENCE PRESENTATION SCHEDULE

— Tuesday, February 13 —

- 8:00am *Welcome and Introductions*, Marjorie Balazs, Chairman SPWCC
- 8:15am *Keynote, “Cleaning And Surface Preparation – The Next Big Challenge?”*
Mark Thirsk, Linx Consulting, LLC
- 9:00am *In-Situ Chemical Monitoring Of Semiconductor Fabrication Chemical Supplies*, Thomas J. Moseman, Philips Semiconductors
- 9:30am *Real Time Metrology For Control Of Cleaning And Etching Solutions*
Eugene Shalyt, ECI Technology
- 10:00am Coffee Break and Exhibits
- 10:30am *Improved Method For The Determination Of Anions In Semiconductor-Grade Chemicals*,
Pranathi Perati, Dionex Corporation
- 11:00am *ICP-MS For High Sensitivity, High Matrix Or Organic Solvent Samples*
Junichi Takahashi, Agilent Technologies, Inc.
- 11:30am *Characterizing Solvent Systems For Wafer Cleaning Through Novel Process Modeling
On A Laboratory Scale*, Mike Quillen, Eastman Chemical Company

- 12:00pm Lunch Sponsored by Thornton, Inc.
- 1:00pm Panel Discussion: *New Cleaning Steps and New Cleaning Issues In 32 nm Processing*, Leader: Steven Verhaverbeke, Applied Materials, Inc.
- 1:45pm *Evaluation Of A New Metal Analyzer For Online Process Control In The Semiconductor Industry*, Vladimir Dozortsev, Trace Detect, Inc.
- 2:15pm *Solution For Reducing Metal Contamination On Silicon Wafers*, Ping Jiang, ATMI, Inc.
- 2:45pm *Reduction Of Aluminum Contamination Using Hydrochloric And Hydrofluoric Acid Mixture In Wet Cleaning Of Silicon Wafer*, Drew Sinha, SUMCO USA
- 3:15pm Coffee Break and Exhibits
- 3:45pm *Trace Metal Analysis of Post CMP Cleaning Solutions*, Haizheng Zhang, Entegris, Inc.
- 4:15pm *The Effect Of Cavitation On Particle Agglomeration In CMP Slurries*, Donald C. Grant, CT Associates, Inc.
- 4:45pm *Effect Of Pump Type On The Health Of Various CMP Slurries*, Mark R. Litchy, CT Associates, Inc.
- 5:15pm Adjourn

—Wednesday, February 14 —

- 8:30am *Welcome and Introductions*, Marjorie Balazs, Chairman SPWCC
- 8:45am *Leaching Study Of Modified PTFE In Ultra Pure Water*, Jason (Jiaxiang) Ren, 3P Corporation
- 9:15am *Urea And Ammonia Removal From De-Ionized Water Via Steam Purification*, Russell Holmes, RASIRC
- 9:45am *Detection And Quantification Of Carboxylic Acid Excursions In UPW Using an On-Line TOC Analyzer*, Zhao Lu, Hach Ultra Analytics
- 10:15am *Coffee Break and Exhibits*
- 10:45am *Micro-Contamination Controlled In Airborne Organics On Electrochemical Plating Process In Semiconductors*, Chia-Ching Wan for S.H. Liu, Taiwan Semiconductor Manufacturing Company, Ltd., Inc.
- 11:15am *Analysis Of Molecular Acid And Base In Mask Relative Materials To Prevent Precipitate Defect For DUV Lithography*, Chia-Ching Wan for Chu-Feng Chen, Taiwan Semiconductor Manufacturing Company, Ltd.
- 11:45am *Phosphine Measurement In Semiconductor Manufacturing Environment By Filter Sampling And HR-ICPMS Analysis*, Chia-Ching Wan, Taiwan Semiconductor Manufacturing Company, Ltd.
- 12:15pm *Table Topics Luncheon Honoring Marjorie Balazs*

- 1:30pm *In-Situ Hydrophobic Silicon Surface Preparation For Manufacture of Bonded Wafers Utilized in Fabrication of RF Microwave Devices*, Iqbal (Izzy) Bansal, M/A-Com, A Tyco Electronics Company
- 2:00pm *Point Of Use Cleaning For Single BEOL Process*, Hiroshi Tomita, TOSHIBA Corporation
- 2:30pm *Development Of A Selective Tantalum Carbide Etchant*, John S. Starzynski, Honeywell Electronic Materials
- 3:00pm *Resist Removal From Semiconductor Wafers*, Sameer Madanshetty, Uncopiers, Inc.
- 3:30pm *Panel Discussion: SPWCC's Growth Path For 2008 and Beyond*
- 4:00pm *Adjourn*

SEMINAR SESSION

Monday, February 12 — 1:00 – 5:00pm

Ensuring The Purity And Reliability of Components Used in Liquid Handling Systems

PRESENTED BY:

GARY VAN SCHOONEVELD AND DON GRANT
CT ASSOCIATES, INC.

Monday, February 12 — 9:00am – 11:00am * NEW TUTORIAL SESSION:

Useful Measurements For Detecting Trace Metal Contaminants In Semiconductor Processing

PRESENTED BY:

MEREDITH BEEBE, TECHNOS INTERNATIONAL AND
FUHE LI, AIR LIQUIDE ELECTRONICS U.S.L.P. – BALAZS

SPECIAL EVENTS:

TUESDAY CONFERENCE LUNCHEON

Thornton, Inc.

Thornton, Inc. will again host an SPWCC Luncheon for all attendees on Tuesday, February 13th! Take advantage of this unique opportunity to network with your peers!

WEDNESDAY TABLE TOPICS LUNCHEON HONORING MARJORIE BALAZS

Please make plans to join us for lunch on Wednesday as we honor Marjorie Balazs

EXHIBITS

See and talk to people showcasing products and services essential to staying on top of emerging technologies and increasing yields!

REGISTRATION INFORMATION

To receive *early* conference registration or be one of our limited number of Exhibitors, **CALL US TODAY @ 650.969.2491** or send us an email to dmiller@spwcc.com